



PATENT
Docket No. 150.0056 0102

#10/E
11/29/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Lee et al.)
Serial No.: 09/560,268)
Filed: 26 April 2000)
For: COMPOSITION FOR SELECTIVELY ETCHING AGAINST COBALT
SILICIDE (As Amended)

Group Art Unit: 1765
Examiner: Deo

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AMENDMENT AND RESPONSE

Assistant Commissioner for Patents
Washington D.C. 20231

Dear Sir:

In response to the Office Action mailed 15 August 2001, please amend the above-identified application as follows:

In the Claims

Please cancel claims 56-61 and add new claims 64-93. The new claims are provided below in clean form. For convenience, all pending claims, including those added hereby, are provided in Appendix A.

64. (New) An etching composition, the composition comprising a mineral acid, a peroxide, and deionized water at a ratio in a range of about 1:1:35 (mineral acid:peroxide:deionized water) to about 1:1:5 (mineral acid:peroxide:deionized water).

65. (New) The etching composition according to claim 64, wherein the mineral acid is HCl and the peroxide is hydrogen peroxide.

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